

MARKED-UP VERSION OF
ENGLISH TRANSLATION OF
INTERNATIONAL APPLICATION
AS ORIGINALLY FILED

DESCRIPTION

Attorney Docket No. 36856.1455

METHOD FOR FORMING THICK FILM PATTERN, METHOD FOR MANUFACTURING
5 ELECTRONIC COMPONENT, AND PHOTOLITHOGRAPHY PHOTSENSITIVE PASTE

~~Technical~~ BACKGROUND OF THE INVENTION

1. Field of the Invention

The present invention relates to a method for forming a
10 thick film pattern by using photolithography, a method for
manufacturing an electronic component, and a photolithography
photosensitive paste to be used for forming a thick film pattern
~~by using the~~ via photolithography.

15 ~~Background~~ 2. Description of the Related Art

As densities have been increased and signal speeds have been
increased for high-frequency electronic apparatuses, patterns,
e.g., wiring conductors, constituting high-frequency circuits
provided in these apparatuses have been required to be fine, have
20 large film thicknesses, have rectangular cross-sectional shapes,
and furthermore, have wiring precision ~~exhibiting~~ with very narrow
ranges of variations in wiring dimensions.

A method for forming a pattern ~~by using~~ via photolithography
has been widely used as a method for forming such a fine pattern.
25 For example, a photosensitive paste containing an inorganic
powder, a photosensitive monomer, a polymer, a

photopolymerization initiator, and the like has been proposed and known as the photosensitive paste to be used therein (for example, ~~Patent Document 1~~).

~~Patent Document 1~~: Japanese Unexamined Patent Application

5 Publication No. 2002-82449).

~~Disclosure of Invention~~

~~Problems to be Solved by the Invention~~

However, in the case where patterns are formed ~~by using~~
10 ~~the~~via photolithography, known photosensitive pastes have a problem in that an adequate photo-curing depth (a depth from a thick film surface, at which the energy of radiated light, e.g., ultraviolet light, travelling in the thick film falls below the minimum energy required for curing a resin due to attenuation by
15 being consumed for curing the resin or being absorbed by the resin component) cannot be ensured.

The inventors of the present invention found that the polymer exerted an influence on this photo-curing depth. The reasons for this are believed to be that (a) the radiated light
20 is refracted and scattered by the polymer and, therefore, it becomes difficult for the ultraviolet light ~~becomes hard to~~ reach the inside of the photosensitive paste, (b) the ultraviolet light is absorbed by the polymer, and (c) when the polymer is contained, the micro-Brownian motion of the monomer in the photosensitive
25 paste is hindered and, thereby, the polymerization becomes hard to proceed.

~~—The~~

SUMMARY OF THE INVENTION

In order to overcome the above-described problems, preferred
embodiments of the present invention ~~is to overcome the above-~~
5 ~~described problems. Accordingly, the object of the present~~
~~invention is to provide~~ a method for forming a thick film pattern,
the method being capable of ~~forming~~ efficiently forming via
photolithography a thick film pattern having a large thickness
and exhibiting high dimension precision and high shape precision
10 ~~by photolithography~~, a method for manufacturing an electronic
component by using the thick film pattern, and a photolithography
photosensitive paste suitable for being used therefor.

~~Means for Solving the Problems~~

15 ~~— In order to overcome the above-described problems, a method~~
~~for forming~~ A method for forming a thick film pattern
according to a thick film pattern preferred embodiment of the
present invention ~~(first aspect) is characterized by including:~~
~~— a film formation step~~ includes the steps of applying to a
20 support a photosensitive paste ~~containing~~ including an inorganic
powder, a photosensitive monomer, and a photopolymerization
initiator and containing substantially no polymer ~~to a support so~~
as to form a photosensitive paste film,†
~~— an exposure step of,~~ subjecting the above-described
25 photosensitive paste film to an exposure treatment,†, and
~~— a development step of developing the above-described~~

photosensitive paste film subjected to the ~~above-described~~ exposure treatment so as to form a predetermined thick film pattern.

A method for forming a thick film pattern ~~of the present invention (second aspect) is characterized by including:~~
~~—— a film formation step~~ according to another preferred embodiment of the present invention includes the steps of applying to a support a photosensitive paste ~~containing~~ including an inorganic powder, a photosensitive monomer, a photopolymerization initiator, and a polymer ~~to a support,~~ wherein a ratio (weight ratio) of the ~~above-described~~ photosensitive monomer to a total amount of the ~~above-described~~ photosensitive monomer and the ~~above-described~~ polymer satisfies the condition represented by the following Formula (1):

$$\text{photosensitive monomer} / (\text{photosensitive monomer} + \text{polymer}) \geq 0.86 \quad (1)$$

so as to form a photosensitive paste film;
~~—— an exposure step of,~~ subjecting the ~~above-described~~ photosensitive paste film to an exposure treatment~~;~~, and
20 ~~—— a development step of developing the above-described~~ photosensitive paste film subjected to the above-described exposure treatment so as to form a predetermined thick film pattern.

A method for forming a thick film pattern according to a
25 ~~third aspect~~ another preferred embodiment of the present invention is characterized in that the contents of the inorganic

powder, the photosensitive monomer, and the photopolymerization initiator constituting the ~~above-described~~ photosensitive paste are within the following ranges of:

inorganic powder: about 60 to about 90 percent by weight,

5 photosensitive monomer: about 5 to about 39 percent by weight, and

photopolymerization initiator: about 1 to about 10 percent by weight.

A method for forming a thick film pattern according to a ~~fourth aspect~~ another preferred embodiment of the present invention is characterized in that a photosensitive paste containing a photosensitive monomer having a double bond concentration within the range of about 8 mmol/g to about 11 mmol/g is preferably used as the ~~above-described~~ photosensitive
15 paste.

A method for forming a thick film pattern according to a ~~fifth aspect~~ further preferred embodiment of the present invention is characterized in that a photosensitive paste ~~containing~~ including a photosensitive monomer having an ethylene
20 oxide structure with a degree of polymerization of about 3 or less is preferably used as the ~~above-described~~ photosensitive paste.

A method for forming a thick film pattern according to a ~~sixth aspect~~ further preferred embodiment of the present invention is characterized in that the ~~above-described~~ photosensitive paste
25 ~~contains~~ includes an ultraviolet absorber.

A method for forming a thick film pattern according to another preferred embodiment of the present invention is characterized in that the photosensitive paste includes a solvent in a proportion of about 5 percent by weight or less.

5 A method for forming a thick film pattern according to a ~~seventh aspect is characterized in that the above-described photosensitive paste contains a solvent in a proportion of 5 percent by weight or less.~~

~~— A method for forming a thick film pattern according to an~~
10 ~~eighth aspect~~ further preferred embodiment of the present invention is characterized in that development is conducted by using an organic solvent in the ~~above-described~~ development step.

15 A method for forming a thick film pattern according to a ~~ninth aspect~~ further preferred embodiment of the present invention is characterized in that the exposure treatment is conducted while the ~~above-described~~ photosensitive paste film and a photomask are ~~disposed in such a way~~ arranged so as to be kept from ~~contact~~ contacting with each other in the ~~above-described~~ exposure step.

20 A method for forming a thick film pattern according to a ~~tenth aspect~~ further preferred embodiment of the present invention is characterized in that the photosensitive paste is subjected to the exposure treatment without using a photomask in the ~~above-described~~ exposure step.

25 A method for manufacturing an electronic component according to a preferred embodiment of the present invention ~~(eleventh~~

aspect) ~~is characterized by including~~ includes the steps of:
—— forming a thick film pattern by the method according to any
one of the first to tenth aspects, above-described preferred
embodiments, and

5 —— then firing the ~~above-described~~ thick film pattern.

A photolithography photosensitive paste according to a
preferred embodiment of the present invention is characterized by
including an inorganic powder, a photosensitive monomer, and a
photopolymerization initiator and containing substantially no
10 polymer.

 A photolithography photosensitive paste according to a
preferred embodiment of the present invention ~~(twelfth aspect) is~~
~~characterized by containing~~ includes ~~an inorganic powder, a~~
~~photosensitive monomer, and a photopolymerization initiator and~~
15 ~~containing substantially no polymer.~~

—— ~~A photolithography photosensitive paste according to the~~
~~present invention (thirteenth aspect) is characterized by~~
~~containing~~

—— ~~an inorganic powder, a photosensitive monomer, a~~
20 ~~photopolymerization initiator, and a polymer,~~

—— wherein a ratio (weight ratio) of the ~~above-described~~
photosensitive monomer to a total amount of the ~~above-described~~
photosensitive monomer and the ~~above-described~~ polymer satisfies
the condition represented by the following Formula (1):

25 photosensitive monomer/(photosensitive monomer + polymer) \geq
0.86 (1).

A photolithography photosensitive paste according to a
~~fourteenth aspect~~ further preferred embodiment of the present
invention is characterized in that

—— the contents of the ~~above-described~~ inorganic powder, the

5 ~~above-described~~ photosensitive monomer, and the ~~above-described~~
photopolymerization initiator are within the following ranges of:

inorganic powder: about 60 to about 90 percent by weight,

photosensitive monomer: about 5 to about 39 percent by
weight, and

10 photopolymerization initiator: about 1 to about 10 percent
by weight.

A photolithography photosensitive paste according to a
~~fifteenth aspect~~ further preferred embodiment of the present
invention is characterized in that the ~~above-described~~

15 photosensitive monomer is a photosensitive monomer having a
double bond concentration within the range of about 8 mmol/g to
about 11 mmol/g.

A photolithography photosensitive paste according to a
~~sixteenth aspect~~ further preferred embodiment of the present

20 invention is characterized in that the ~~above-described~~
photosensitive monomer is a photosensitive monomer having an
ethylene oxide structure with a degree of polymerization of about
3 or less.

A photolithography photosensitive paste according to a
25 ~~seventeenth aspect~~ further preferred embodiment of the present
invention is characterized by ~~containing~~ including an ultraviolet

absorber.

A photolithography photosensitive paste according to an
eighteenth-aspect a further preferred embodiment of the present
invention is characterized by ~~containing~~including a solvent in a
5 proportion of about 5 percent by weight or less.

~~Advantages~~

In the method for forming a thick film pattern according to
a preferred embodiment of the present invention ~~(first aspect)~~,
10 the photosensitive paste ~~containing~~including the inorganic powder,
the photosensitive monomer, and the photopolymerization initiator
and containing substantially no polymer is applied to the support
so as to form the photosensitive paste film, the resulting
photosensitive paste film is subjected to the exposure treatment,
15 and thereafter, the development is conducted so as to form a
predetermined thick film pattern. Therefore, it becomes possible
to ~~form~~ efficiently form a thick film pattern having a large
thickness and exhibiting high dimension precision and high shape
precision.

20 That is, since the photosensitive paste containing
substantially no polymer is used, in the exposure step,
refraction, scattering, absorption, and the like of the radiated
light by the polymer do not occur, the ultraviolet light easily
reaches the inside of the photosensitive paste film, the micro-
25 Brownian motion of the photosensitive monomer is not hindered by
the polymer, and the polymerization is prevented from becoming

hard to proceed. Consequently, it becomes possible to form a thick film pattern having a large thickness, a high hardness, and a high aspect ratio and exhibiting high dimension precision and high shape precision.

5 In various preferred embodiments of the present invention, that a photosensitive paste "contains substantially no polymer" ~~refers to~~ means that the present invention includes the case where a very small amount of polymer is contained as an impurity in a photosensitive paste.

10 In the case where the photosensitive paste containing the polymer is used as in the method for forming a thick film pattern according to a preferred embodiment of the present invention ~~(second aspect)~~ as well, when a ratio (weight ratio) of the photosensitive monomer to a total amount of the photosensitive
15 monomer and the polymer satisfies the condition represented by $\text{photosensitive monomer} / (\text{photosensitive monomer} + \text{polymer}) \geq 0.86$, that is, when the ratio of the polymer to the total amount of the photosensitive monomer and the polymer is less than about 0.14 on a weight ratio basis (less than about 14 percent by weight), in
20 the exposure step, refraction, scattering, absorption, and the like of the radiated light by the polymer can be reduced, the ultraviolet light easily reaches the inside of the photosensitive paste film, and the micro-Brownian motion of the photosensitive monomer is prevented from being hindered by the polymer.
25 Consequently, it becomes possible to form reliably a thick film pattern having a large thickness and exhibiting high dimension

precision and high shape precision.

When the contents of the inorganic powder, the photosensitive monomer, and the photopolymerization initiator constituting the photosensitive paste are specified to be within
5 the following ranges—~~of~~:

inorganic powder: about 60 to about 90 percent by weight,
photosensitive monomer: about 5 to about 39 percent by weight, and

photopolymerization initiator: about 1 to about 10 percent
10 by weight

~~as in the method for forming a thick film pattern according to the third aspect,~~ the value of photo-curing depth of the photosensitive paste can be increased. Consequently, it becomes possible to ~~form~~ efficiently form a thick film pattern having a
15 large thickness and exhibiting high dimension precision and high shape precision by using the ~~above-described~~ photosensitive paste.

When the photosensitive paste containing a photosensitive monomer having a double bond concentration within the range of about 8 mmol/g to about 11 mmol/g is used as the photosensitive
20 paste, ~~as in the method for forming a thick film pattern according to the fourth aspect,~~ it becomes possible to increase the photo-curing depth and, therefore, the present invention is allowed to become more effective.

When the photosensitive paste containing a photosensitive
25 monomer having an ethylene oxide structure with a degree of polymerization of about 3 or less is used as the photosensitive

paste, ~~as in the method for forming a thick film pattern according to the fifth aspect,~~ it becomes possible to increase the value of photo-curing depth. This is preferable.

When the photosensitive paste ~~containing~~including an ultraviolet absorber is used, ~~as in the method for forming a thick film pattern according to the sixth aspect,~~ it becomes possible to achieve a deeper photo-curing depth by a small amount of exposure and, therefore, a thick film pattern having a large thickness and exhibiting high dimension precision and high shape precision can be formed efficiently.

When the photosensitive paste ~~containing~~including a solvent in a proportion of about 5 percent by weight or less is used, ~~as in the method for forming a thick film pattern according to the seventh aspect,~~ a drying step is allowed to become unnecessary or the drying step is allowed to be simplified and, therefore, the present invention is allowed to become more effective.

When the development is conducted by using the organic solvent in the development step, ~~as in the method for forming a thick film pattern according to the eighth aspect,~~ impurities do not enter the pattern, and a rinse step is allowed to become unnecessary or the rinse step is allowed to be simplified. Therefore, the development can easily and speedily be conducted and the present invention is allowed to become more effective.

When the exposure treatment is conducted while the photosensitive paste film and the photomask are disposed in such a way as to be kept from ~~contact~~contacting with each other in the

exposure step, ~~as in the method for forming a thick film pattern according to the ninth aspect,~~ the photosensitive paste film is prevented from being damaged due to contact with the photomask. Therefore, it becomes possible to form a highly reliable thick
5 film pattern.

When the photosensitive paste is subjected to the exposure treatment without using a photomask in the exposure step, ~~as in the method for forming a thick film pattern according to the tenth aspect,~~ the photomask ~~is allowed to become~~ becomes
10 unnecessary. Consequently, the cost can be reduced, the manufacturing step is allowed to be simplified and, therefore, the present invention is allowed to become more effective.

In the method for manufacturing an electronic component according to one of the preferred embodiments of the present
15 invention ~~(eleventh aspect)~~, after the thick film pattern is formed by the method according to any one of the ~~first to tenth aspects~~ other preferred embodiments of the present invention, the resulting thick film pattern is fired. Consequently, it becomes possible to produce efficiently and reliably a high-performance,
20 highly reliable electronic component provided with a fine pattern.

The photolithography photosensitive paste according to a preferred embodiment of the present invention ~~(twelfth aspect)~~ ~~contains~~ includes the inorganic powder, the photosensitive monomer, and the photopolymerization initiator and contains substantially
25 no polymer. Consequently, in the exposure step, since refraction, scattering, absorption, and the like of the radiated light by the

polymer do not occur, the ultraviolet light easily reaches the inside of the photosensitive paste film, the micro-Brownian motion of the photosensitive monomer is not hindered by the polymer, and the polymerization tends to proceed. Therefore, it becomes possible to reliably form a thick film pattern exhibiting high dimension precision and high shape precision by using the photolithography photosensitive paste according to the present invention.

In the case where the polymer is ~~contained, as in the photolithography photosensitive paste according to the present invention (thirteen aspect) as well~~included, when the ratio (weight ratio) of the photosensitive monomer to a total amount of the photosensitive monomer and the polymer satisfies the condition represented by $\text{photosensitive monomer} / (\text{photosensitive monomer} + \text{polymer}) \geq 0.86$, that is, when the ratio of the polymer to the total amount of the photosensitive monomer and the polymer is less than about 0.14 on a weight ratio basis (less than about 14 percent by weight), in the exposure step, refraction, scattering, absorption, and the like of the radiated light by the polymer can be reduced, the ultraviolet light easily reaches the inside of the photolithography photosensitive paste film, and the micro-Brownian motion of the photosensitive monomer is prevented from being hindered by the polymer. Consequently, it becomes possible to reliably form a thick film pattern having a large thickness and exhibiting high dimension precision and high shape precision.

When the contents of the inorganic powder, the photosensitive monomer, and the photopolymerization initiator constituting the ~~above-described~~ photolithography photosensitive paste are ~~specified to be within the~~ following ranges of:

5 inorganic powder: about 60 to about 90 percent by weight,

photosensitive monomer: about 5 to about 39 percent by weight, and

photopolymerization initiator: about 1 to about 10 percent by weight,

10 ~~as in the photolithography photosensitive paste according to the fourteenth aspect,~~ a photolithography photosensitive paste having a large value of photo-curing depth can be produced. Consequently, it becomes possible to form efficiently a thick film pattern having a large thickness and exhibiting high
15 dimension precision and high shape precision by using the ~~above-described~~ photolithography photosensitive paste.

When the photolithography photosensitive paste contains the photosensitive monomer having a double bond concentration within the range of about 8 mmol/g to about 11 mmol/g as the
20 photosensitive monomer, ~~as in the fifteenth aspect,~~ it becomes possible to increase the photo-curing depth and, therefore, the present invention is allowed to become more effective.

When the photolithography photosensitive paste ~~contains~~includes the photosensitive monomer having an ethylene
25 oxide structure with a degree of polymerization of about 3 or less as the photosensitive paste, ~~as in the sixteenth aspect,~~ it

becomes possible to increase the value of photo-curing depth particularly and, therefore, the present invention is allowed to become more effective.

When the photolithography photosensitive paste
5 ~~contains~~includes an ultraviolet absorber, ~~as in the seventeenth aspect,~~ it becomes possible to achieve a deeper photo-curing depth by a small amount of exposure and, therefore, a thick film pattern having a large thickness and exhibiting high dimension precision and high shape precision can be formed efficiently.
10 Consequently, the present invention is allowed to become more effective.

When the photolithography photosensitive paste contains a solvent in a proportion of about 5 percent by weight or less, ~~as in the eighteenth aspect,~~ it becomes possible to form a thick
15 film pattern without conducting drying or with drying for a minimum drying time. Therefore, the present invention is allowed to become more effective.

~~Brief Description of the Drawings~~

20 ~~{Fig. 1}~~— Other features, elements, steps, characteristics and advantages of the present invention will become more apparent from the following detailed description of preferred embodiments thereof with reference to the attached drawings.

BRIEF DESCRIPTION OF THE DRAWINGS

Figs. 1(a) to (c) are diagrams showing a method for forming a thick film pattern by a method according to ~~ana~~ a preferred embodiment of the present invention.

5 ~~[Fig. 2]~~ Figs. 2(a) to (d) are diagrams showing a method for forming a thick film pattern by another method ~~of~~ the according to a further preferred embodiment of the present invention.

10 ~~[Fig. 3]~~ Fig. 3 is a sectional view showing an electronic component (ceramic multilayer substrate) according to ~~an~~ another preferred embodiment of the present invention.

~~[Fig. 4]~~ Fig. 4 is a perspective view showing an appearance of a chip coil according to ~~an~~ another preferred embodiment of the present invention.

15 ~~[Fig. 5]~~ Fig. 5 is a perspective exploded view showing a configuration of the chip coil shown in Fig. 4.

~~Reference Numerals~~ DETAILED DESCRIPTION OF PREFERRED EMBODIMENTS

— L — ~~line-shaped pattern (thick film pattern)~~
20 — S — ~~space~~
— 1 — ~~substrate (alumina substrate)~~
— 2 — ~~film (photosensitive paste film)~~
— 3 — ~~photomask~~
— 5 — ~~PET film~~
25 — 6 — ~~green sheet~~
— 11 — ~~ceramic multilayer substrate~~

- 5
10
15
- ~~12a, 12b, 12c, 12d, 12e, 12f~~ insulator layer
 - ~~13a, 13b~~ dielectric layer
 - ~~15~~ inner layer copper pattern
 - ~~16~~ via hole
 - ~~17~~ surface layer copper pattern
 - ~~20~~ chip component
 - ~~21~~ thick film resistor
 - ~~22~~ semiconductor IC
 - ~~31~~ chip coil
 - ~~32~~ component body
 - ~~33~~ insulating substrate
 - ~~34, 35, 36, 37~~ insulator film
 - ~~38, 39, 40, 41~~ conductor film
 - ~~42, 43~~ external terminal
 - ~~44, 45, 46~~ via hole connection portion

~~Best Mode for Carrying Out the Invention~~

When a method for forming a thick film pattern according to a preferred embodiment of the present invention is carried out, it is desirable that a photosensitive paste usually having inorganic powder, photosensitive monomer, and photopolymerization initiator have contents within the following ranges of:

- (a) inorganic powder: about 60 to about 90 percent by weight
- (b) photosensitive monomer: about 5 to about 39 percent by weight
- (c) photopolymerization initiator: about 1 to about 10

percent by weight,
_respectively,~~is used~~.

The content of the inorganic powder is specified to be within the range of about 60 to about 90 percent by weight and, thereby, in the case where a metal powder is used as the inorganic powder, it becomes possible to prevent an occurrence of poor electrical conductivity (increase in conductor resistance). In the case where a ceramic material powder or a glass powder is used as the inorganic powder, it becomes possible to prevent an occurrence of poor insulation.

Furthermore, when the content of the inorganic powder is specified to be within the range of about 60 to about 90 percent by weight, an excessive increase in viscosity of the photosensitive paste, difficulty of handling, deterioration of printability, and the like do not occur, and it becomes possible to keep good photo-curability. In addition, reduction in strength of a cured material and embrittlement of a cured material can be ~~avoided~~prevented.

With respect to the range of particle diameter of the inorganic powder, when the average particle diameter is specified to be within the range of about 0.1 μ m to about 10 μ m, agglomeration of particles is suppressed, good dispersibility is maintained, and it becomes possible to produce a fine pattern. In addition, it becomes possible to produce a photosensitive paste having adequate photo-curability and, therefore, this is preferable. It is more preferable that an inorganic powder

having an average particle diameter of about 0.5 ~~to~~ μm to about 5 μm is used.

Preferably, a spherical inorganic powder is used. However, an inorganic powder in the shape of foil, a granule, a block, a flat material, a plate, a rod, a needle, and the like can also be used, and the shape can be selected appropriately depending on a thick film pattern to be formed.

Alternatively, an electrically conductive powder, a ceramic powder, a glass powder, and the like can be used as the inorganic powder.

Examples of usable electrically conductive powder include Ag, Au, Pt, Pd, Cu, Ni, W, Al, and Mo, and these can also be used in combination. An alloy containing at least one type of the above-described metals can also be used. Furthermore, a metal powder provided with an oxide coating, a nitride coating, or a silicide coating can also be used.

Examples of usable ceramic powders include an oxide, a boride, a nitride, a silicide, and the like of at least one type of metal selected from the group consisting of Al, Ag, Cu, Ni, Ti, Ba, Pb, Zr, Mn, Cr, Sr, Fe, Y, Nb, La, Si, Zn, Bi, B and Ru. A glass composite based ceramic powder can also be used.

Known glass powders, e.g., a borosilicate based glass powder, can be used as the glass powder. More specifically, examples of usable glass powders include glass powders of SiO_2 -PbO base, SiO_2 -ZnO base, SiO_2 - Bi_2O_3 base, SiO_2 - K_2O base, SiO_2 - Na_2O base, SiO_2 -PbO- B_2O_3 base, SiO_2 -ZnO- B_2O_3 base, SiO_2 - Bi_2O_3 - B_2O_3 base, SiO_2 - K_2O -

B₂O₃ base, and SiO₂-Na₂O-B₂O₃ base.

It is possible that the above-described substances are used as the inorganic powder by mixing, that is, Ag and glass can be used by mixing, for example.

5 It is desirable that the ratio of the photosensitive monomer is within the range of about 5 to about 39 percent by weight, as described above. This is because it becomes possible to prevent reduction in photo-curability and the resulting reduction in strength of a cured material (embrittlement of a cured material)
10 by specifying the proportion of the photosensitive monomer to be within the range of about 5 to about 39 percent by weight and, in addition, it becomes possible to avoid excessive reduction in the proportion of the inorganic powder, while these are preferable.

 Examples of photosensitive monomers include stearyl acrylate,
15 tetrahydrofurfuryl acrylate, lauryl acrylate, 2-phenoxyethyl acrylate, isodecyl acrylate, isooctyl acrylate, tridecyl acrylate, caprolactone acrylate, ethoxylated nonylphenol acrylate, 1,4-butanediol diacrylate, diethylene glycol diacrylate, tetraethylene glycol diacrylate, triethylene glycol diacrylate,
20 ethoxylated bisphenol A diacrylate, propoxylated neopentyl glycol diacrylate, tris(2-hydroxyethyl)isocyanurate triacrylate, propoxylated trimethylolpropane triacrylate, propoxylated glyceryl triacrylate, pentaerythritol tetraacrylate, tetrahydrofurfuryl methacrylate, cyclohexyl methacrylate,
25 isodecyl methacrylate, lauryl methacrylate, triethylene glycol dimethacrylate, tetraethylene glycol dimethacrylate, 1,9-

nonanediol diacrylate, 1,6-hexanediol dimethacrylate, neopentyl glycol dimethacrylate, ethoxylated bisphenol A dimethacrylate, ethoxylated isocyanuric acid diacrylate, ethoxylated paracumylphenol acrylate, ethylhexylcarbitol acrylate, N-vinyl-2-pyrrolidone, isobornyl acrylate, and polypropylene glycol diacrylate.

When a monomer having a double bond concentration within the range of about 8 mmol/g to about 11 mmol/g is used as the photosensitive monomer, in particular, it becomes possible to improve the photo-curing depth.

Examples of photosensitive monomers having a double bond concentration within the range of about 8 mmol/g to about 11 mmol/g include hexanediol triacrylate, tripropylene glycol triacrylate, trimethylolpropane triacrylate, 1,3-butanediol diacrylate, pentaerythritol triacrylate, ditrimethylolpropane tetraacrylate, dipentaerythritolhydroxy pentaacrylate, ethoxylated pentaerythritol tetraacrylate, ethylene glycol dimethacrylate, 1,4-butanediol dimethacrylate, diethylene glycol dimethacrylate, 1,3-butylene glycol dimethacrylate, trimethylolpropane triacrylate, dipentaerythritol pentaacrylate, and dipentaerythritol hexaacrylate.

When a photosensitive paste containing a photosensitive monomer having an ethylene oxide structure with a degree of polymerization of about 3 or less is used, it becomes possible to improve the photo-curing depth. That is, in the case where the degree of polymerization of the ethylene oxide structure is about

3 or less and, therefore, is low, the effect of improving the photo-curing depth is enhanced.

Examples of photosensitive monomers having an ethylene oxide structure with a degree of polymerization of about 3 or less
5 include ethoxylated (ethylene oxide-modified) compounds, e.g., ethoxylated trimethylolpropane triacrylate, and polyethylene glycol diacrylate.

It is desirable that the photopolymerization initiator within the range of about 1 to about 10 percent by weight is
10 ~~contained.~~included. When the photopolymerization initiator is specified to be within the range of about 1 to about 10 percent by weight, poor photo-curability and reduction in hardness of the cured material due to shortage of photopolymerization initiator are avoided, and it becomes possible to form a pattern having a
15 high aspect ratio. In addition, it becomes possible to ~~avoid~~prevent the energy from not reaching the inside due to excessive absorption of the ultraviolet light by the photosensitive paste. Consequently, it becomes possible to reliably form a pattern having an adequate thickness and
20 exhibiting high hardness of cured material and, therefore, this is preferable.

Examples of photopolymerization initiators suitable for use in the present invention include benzil, benzoin ethyl ether, benzoin isobutyl ether, benzoin isopropyl ether, benzophenone,
25 benzoylbenzoic acid, methyl benzoyl benzoate, 4-benzoyl-4'-methyldiphenyl sulfide, benzyl dimethyl ketal, 2-n-butoxy-4-

dimethylaminobenzoate, 2-chlorothioxanthone, 2,4-diethylthioxanthone, 2,4-diisopropylthioxanthone, isopropylthioxanthone, 2-dimethylaminoethyl benzoate, ethyl p-dimethylaminobenzoate, isoamyl p-dimethylaminobenzoate, 3,3'-dimethyl-4-methoxybenzophenone, 2,4-dimethylthioxanthone, 1-(4-dodecylphenyl)-2-hydroxy-2-methylpropane-1-on, 2,2-dimethoxy-1,2-diphenylethane-1-on, hydroxycyclohexyl phenyl ketone, 2-hydroxy-2-methyl-1-phenylpropane-1-on, 1-[4-(2-hydroxyethoxy)-phenyl]-2-methyl-1-propane-1-on, 2-methyl-1-[4-(methylthio)phenyl]-2-morpholinopropane-1-on, methylbenzoylformate, 1-phenyl-1,2-propanedion-2-(o-ethoxycarbonyl)oxime, 2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-1-butanone, bis(2,6-dimethoxybenzoyl)-2,4,4-trimethylpentylphosphine oxide, bis(2,4,6-trimethylbenzoyl)phenylphosphine oxide, bis(2,4,6-trimethylbenzoyl)-2,4,4-trimethylpentylphosphine oxide, bis(2,6-dichlorobenzoyl)-2,4,4-trimethylpentylphosphine oxide, 1-(4-isopropylphenyl)-2-hydroxy-2-methylpropane-1-on, 1,2-diphenylethanedion, and methylphenyl glyoxylate. These photopolymerization initiators may be used alone or at least two types thereof may be used at the same time.

In some cases, photosensitizers may be added. Examples of photosensitizers include p-dimethylaminobenzoic acid isoamyl ester and p-dimethylaminobenzoic acid ethyl ester.

A photosensitive paste containing a solvent in a proportion of about 5 percent by weight or less can be used.

Specific examples of solvents include alcohols, e.g.,

ethanol and isopropyl alcohol; ketones, e.g., methyl ethyl ketone; and aromatic compounds, e.g., xylene. These solvents can also be used by mixing.

It is basically desirable that no solvent is contained from the viewpoint of eliminating the need for a drying step. However, in the case where a solvent is added for the purpose of adjusting the viscosity of the photosensitive paste or in the case where a solvent is added accompanying an additive when the additive or the like is added, no specific problem occurs as long as the proportion of the solvent is about 5 percent by weight or less. Even when the content of the solvent exceeds about 5 percent by weight, the operation and the effect of various preferred embodiments of the present invention is not always impaired, although the drying step is required.

In preferred embodiments of the present invention, if necessary, the photosensitive paste can also ~~contain~~include additives, e.g., a thixotropic agent (thickener, anti-settling agent), a dispersing agent, a polymerization inhibitor (radical trapping agent), and an ultraviolet absorber (dye, pigment, HALS = hindered amine based light stabilizer).

~~FIRST EMBODIMENT~~

The features of the present invention will be described below in further detail with reference to ~~the examples of various~~ preferred embodiments thereof.

†

Example No. 1†

<Preparation of ~~Photosensitive~~photosensitive paste P1>

The following materials were blended and kneaded, so that ~~Photosensitive~~photosensitive paste P1 containing no polymer was prepared.

5 Ag powder (average particle diameter = 2.8 μm): 75.0 percent
by weight

 dipentaerythritol hexaacrylate (photosensitive monomer):
17.7 percent by weight

 2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
10 1.6 percent by weight

 2,4-diethylthioxanthone: 0.5 percent by weight

 2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
2.2 percent by weight

 pentamethylene glycol: 3.0 percent by weight

15

<Formation of film by using ~~Photosensitive paste~~ photosensitive
paste P1 and evaluation of properties>

 The photo-curing depth of the resulting ~~Photosensitive paste~~
photosensitive paste P1 was 18.9 μm at an amount of exposure of
20 400 mJ/cm^2 .

 As shown in Fig. 1(a), a film (photosensitive paste film) 2
having a thickness of 17.0 μm was formed on a substrate (an
alumina substrate in the present Example) 1 serving as a support
through screen printing by using this
25 ~~Photosensitive~~photosensitive paste P1. Thereafter, the
photosensitive paste film 2 was cured by application of

ultraviolet light under a condition of 400 mJ/cm^2 through a photomask 3, as shown in Fig. 1(b), and uncured portions were removed with ethanol, as shown in Fig. 1(c), so that a thick film pattern was produced, in which a plurality of line-shaped patterns L having the same width were disposed with spaces S therebetween. The lower limit of the pattern width of the line-shaped patterns L was $20 \text{ }\mu\text{m}$, and the lower limit of the space width of the spaces S was $20 \text{ }\mu\text{m}$ (hereafter represented by, for example, a minimum $L/S = 20/20 \text{ }\mu\text{m}$).

The aspect ratio (a ratio of a height dimension to a base dimension (height dimension/base dimension) of a cross section of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.80.

Subsequently, a film having a thickness of $25 \text{ }\mu\text{m}$ was formed on an alumina substrate by using this ~~Photosensitive~~photosensitive paste P1 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers hardness of this coating film measured 24.6 Hv .

†

Example No. 2†

<Preparation of ~~Photosensitive~~photosensitive paste P2>

The following materials were blended and kneaded, so that ~~Photosensitive~~photosensitive paste P2 containing no polymer was prepared.

Ag powder (average particle diameter = 2.8 μm): 80.0 percent
by weight

dipentaerythritol hexaacrylate (photosensitive monomer):
14.8 percent by weight

5 2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
2.0 percent by weight

2,4-diethylthioxanthone: 0.9 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
2.3 percent by weight

10
<Formation of film by using ~~Photosensitive~~photosensitive paste P2
and evaluation of properties>

The photo-curing depth of the resulting
~~Photosensitive~~photosensitive paste P2 was 16.2 μm at an amount of
15 exposure of 400 mJ/cm^2 . A film having a thickness of 16.0 μm was
formed on an alumina substrate through screen printing by using
this ~~Photosensitive~~photosensitive paste P2. Thereafter, the
resulting film was cured by application of ultraviolet light
under a condition of 400 mJ/cm^2 through a photomask, and uncured
20 portions were removed with ethanol. As a result, the minimum L/S
was 25/25 μm .

The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.69.

Subsequently, a film having a thickness of 25 μm was formed
25 on an alumina substrate by using this
~~Photosensitive~~photosensitive paste P2 through screen printing,

and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers hardness of this coating film measured 15.2 Hv .

5 †

Example No. 3†

<Preparation of ~~Photosensitive~~photosensitive paste P3>

The following materials were blended and kneaded, so that
10 ~~Photosensitive~~photosensitive paste P3 containing no polymer was prepared.

Ag powder (average particle diameter = $2.8 \text{ }\mu\text{m}$): 85.0 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer):
15 10.9 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
1.2 percent by weight

2,4-diethylthioxanthone: 0.4 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
20 1.2 percent by weight

ethylcarbitol acetate: 1.3 percent by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste P3 and evaluation of properties>

25 The photo-curing depth of the resulting
~~Photosensitive~~photosensitive paste P3 was $12.8 \text{ }\mu\text{m}$ at an amount of

exposure of 400 mJ/cm^2 . A film having a thickness of $12.0 \text{ }\mu\text{m}$ was formed on an alumina substrate through screen printing by using this ~~Photosensitive~~photosensitive paste P3. Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with ethanol. As a result, the minimum L/S was $25/25 \text{ }\mu\text{m}$.

The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.61.

Subsequently, a film having a thickness of $25 \text{ }\mu\text{m}$ was formed on an alumina substrate by using this ~~Photosensitive~~photosensitive paste P3 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers hardness of this coating film measured 10.6 Hv .

†

Example No. 4†

<Preparation of ~~Photosensitive~~photosensitive paste P4>

The following materials were blended and kneaded, so that ~~Photosensitive~~photosensitive paste P4 containing no polymer was prepared.

Ag powder (average particle diameter = $2.8 \text{ }\mu\text{m}$): 71.0 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer): 11.0 percent by weight

trimethylolpropane EO-modified (degree of polymerization $n =$
1) triacrylate (photosensitive monomer): 11.0 percent by weight
2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
1.7 percent by weight
5 2,4-diethylthioxanthone: 1.5 percent by weight
2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
2.3 percent by weight
thixotropic agent: 1.5 percent by weight

10 <Formation of film by using ~~Photosensitive~~photosensitive paste P4
and evaluation of properties>

The photo-curing depth of the resulting
~~Photosensitive~~photosensitive paste P4 was 22.1 μm at an amount of
exposure of 400 mJ/cm^2 . A film having a thickness of 20.8 μm was
15 formed on an alumina substrate through screen printing by using
this ~~Photosensitive~~photosensitive paste P4. Thereafter, the
resulting film was cured by application of ultraviolet light
under a condition of 400 mJ/cm^2 through a photomask, and uncured
portions were removed with acetone. As a result, the minimum L/S
20 was 25/20 μm .

The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.68.

Subsequently, a film having a thickness of 25 μm was formed
on an alumina substrate by using this
25 ~~Photosensitive~~photosensitive paste P4 through screen printing,
and the resulting film was cured by application of ultraviolet

light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers hardness of this coating film measured 30.2 Hv .

†Example No. 5†

5 <Preparation of ~~Photosensitive~~photosensitive paste P5>

The following materials were blended and kneaded, so that ~~Photosensitive~~photosensitive paste P5 containing no polymer was prepared.

10 Ag powder (average particle diameter = $2.8 \text{ }\mu\text{m}$): 75.0 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer): 9.5 percent by weight

trimethylolpropane EO-modified (degree of polymerization $n = 1$) triacrylate (photosensitive monomer): 9.5 percent by weight

15 2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on: 2.8 percent by weight

2,4-diethylthioxanthone: 0.7 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1: 2.5 percent by weight

20 <Formation of film by using ~~Photosensitive~~photosensitive paste P5 and evaluation of properties>

The photo-curing depth of the resulting ~~Photosensitive~~photosensitive paste P5 was $18.5 \text{ }\mu\text{m}$ at an amount of exposure of 400 mJ/cm^2 . A film having a thickness of $18.1 \text{ }\mu\text{m}$ was formed on an alumina substrate through screen printing by using

25

this ~~Photosensitive~~photosensitive paste P5. Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with acetone. As a result, the minimum L/S
5 was $25/25 \text{ }\mu\text{m}$.

The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.62.

Subsequently, a film having a thickness of $25 \text{ }\mu\text{m}$ was formed on an alumina substrate by using this

10 ~~Photosensitive~~photosensitive paste P5 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers hardness of this coating film measured 26.5 Hv .

15 †

Example No. 6†

<Preparation of ~~Photosensitive~~photosensitive paste P6>

The following materials were blended and kneaded, so that
~~Photosensitive~~photosensitive paste P6 containing no polymer was
20 prepared.

Ag powder (average particle diameter = $2.8 \text{ }\mu\text{m}$): 80.0 percent
by weight

dipentaerythritol hexaacrylate (photosensitive monomer): 7.6
percent by weight

25 trimethylolpropane EO-modified (degree of polymerization $n = 1$) triacrylate (photosensitive monomer): 7.6 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:

1.5 percent by weight

2,4-diethylthioxanthone: 0.6 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:

5 2.0 percent by weight

pentamethylene glycol: 0.7 percent by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste P6 and evaluation of properties>

10 The photo-curing depth of the resulting ~~Photosensitive~~photosensitive paste P6 was 17.0 μm at an amount of exposure of 400 mJ/cm^2 . A film having a thickness of 16.8 μm was formed on an alumina substrate through screen printing by using this ~~Photosensitive~~photosensitive paste P6. Thereafter, the
15 resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with acetone. As a result, the minimum L/S was 30/30 μm .

The aspect ratio of the pattern was determined from
20 dimensions after firing. The resulting aspect ratio was 0.55.

Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this ~~Photosensitive~~photosensitive paste P6 through screen printing, and the resulting film was cured by application of ultraviolet
25 light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers

hardness of this coating film measured 17.1 Hv.

†

Example No. 7†

<Preparation of ~~Photosensitive~~photosensitive paste P7>

5 The following materials were blended and kneaded, so that
~~Photosensitive~~photosensitive paste P7 containing no polymer was
prepared.

Ag powder (average particle diameter = 2.8 μm): 80.0 percent
by weight

10 Si-B based glass powder (average particle diameter = 1.5
 μm): 2.4 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer):
15.0 percent by weight

15 2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
1.5 percent by weight

2,4-diethylthioxanthone: 0.6 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
0.5 percent by weight

20 <Formation of film by using ~~Photosensitive paste~~photosensitive
paste P7 and evaluation of properties>

The photo-curing depth of the resulting
~~Photosensitive~~photosensitive paste P7 was 15.2 μm at an amount of
exposure of 400 mJ/cm^2 .

25 As shown in Fig. 2(a), a film (photosensitive paste film) 2
having a thickness of 14.7 μm was formed on a PET film 5 serving

as a support through screen printing by using this
~~Photosensitive~~photosensitive paste P7. Thereafter, the resulting
film 2 was cured by application of ultraviolet light under a
condition of 400 mJ/cm^2 through a photomask, and uncured portions
5 were removed with ethanol, as shown in Fig. 2(b). As a result,
the minimum ratio of the line-shaped pattern L to the space S
(L/S) was $25/30 \text{ }\mu\text{m}$.

Subsequently, the pattern (thick film pattern) L disposed on
this PET film 5 was turned upside down and, as shown in Fig. 2(c),
10 was pressed and transferred to a green sheet 6 by using a
thermocompression bonding device under the condition of 60°C , 0.5 MPa , and 60 seconds, so that a pattern (thick film pattern) L was
formed on the green sheet 6, as shown in Fig. 2(d). This pattern
L was fired and the width and the thickness of the pattern were
15 observed with a laser microscope. The resulting aspect ratio was
0.51.

A film having a thickness of $25 \text{ }\mu\text{m}$ was formed on an alumina
substrate by using this ~~Photosensitive~~photosensitive paste P7
through screen printing, and the resulting film was cured by
20 application of ultraviolet light at 400 mJ/cm^2 . This operation
was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$
was formed. The Vickers hardness of this coating film measured
14.8 Hv.

†

25 Example No. 8†

<Preparation of ~~Photosensitive~~photosensitive paste P8>

The following materials were blended and kneaded, so that ~~Photosensitive~~photosensitive paste P8 containing no polymer was prepared.

Ag powder (average particle diameter = 2.8 μm): 56.3 percent
5 by weight

Al_2O_3 -coated Ag (average particle diameter = 2.0 μm): 18.8 percent by weight

Si-B based glass powder (average particle diameter = 1.5 μm): 2.4 percent by weight

10 dipentaerythritol hexaacrylate (photosensitive monomer): 16.5 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on: 1.5 percent by weight

2,4-diethylthioxanthone: 0.9 percent by weight

15 2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1: 2.3 percent by weight

dipropylene glycol monomethyl ether: 1.3 percent by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste P8 and evaluation of properties>

20 The photo-curing depth of the resulting ~~Photosensitive~~photosensitive paste P8 was 13.9 μm at an amount of exposure of 400 mJ/cm^2 . A film having a thickness of 13.0 μm was formed on a PET film serving as a support through screen printing by using this ~~Photosensitive~~photosensitive paste P8. Thereafter,
25 the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured

portions were removed with ethanol. As a result, the minimum L/S was 25/30 μm .

Subsequently, the pattern disposed on this PET film was turned upside down, and was pressed and transferred to a green sheet by using a thermocompression bonding device under the condition of 60°C, 0.5 MPa, and 60 seconds. The resulting pattern was fired and the width and the thickness of the pattern were observed with a laser microscope. The resulting aspect ratio was 0.45.

A film having a thickness of 25 μm was formed on an alumina substrate by using this ~~Photosensitive~~photosensitive paste P8 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm². This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 15.4 Hv.

~~{Example No. 9}~~

<Preparation of ~~Photosensitive~~photosensitive paste P9>

The following materials were blended and kneaded, so that ~~Photosensitive~~photosensitive paste P9 containing no polymer was prepared.

Cu powder (average particle diameter = 2.5 μm): 77.0 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer):

14.0 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:

1.0 percent by weight

2,4-diethylthioxanthone: 0.4 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:

1.6 percent by weight

5 dipropylene glycol monomethyl ether: 3.0 percent by weight

pentamethylene glycol: 3.0 percent by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste P9
and evaluation of properties>

10 The photo-curing depth of the resulting
~~Photosensitive~~photosensitive paste P9 was 15.8 μm at an amount of
exposure of 400 mJ/cm^2 . A film having a thickness of 15.1 μm was
formed on an alumina substrate through screen printing by using
this ~~Photosensitive~~photosensitive paste P9. Thereafter, the
15 resulting film was cured by application of ultraviolet light
under a condition of 400 mJ/cm^2 through a photomask, and uncured
portions were removed with ethanol. As a result, the minimum L/S
was 30/30 μm .

The aspect ratio of the pattern was determined from
20 dimensions after firing. The resulting aspect ratio was 0.59.

Subsequently, a film having a thickness of 25 μm was formed
on an alumina substrate by using this
~~Photosensitive~~photosensitive paste P9 through screen printing,
and the resulting film was cured by application of ultraviolet
25 light at 400 mJ/cm^2 . This operation was repeated, so that a
paste film having a thickness of 100 μm was formed. The Vickers

hardness of this coating film measured 17.8 Hv.

†

Example No. 10†

<Preparation of ~~Photosensitive~~photosensitive paste P10>

5 The following materials were blended and kneaded, so that
~~Photosensitive~~photosensitive paste P10 containing no polymer was
prepared.

 Cu powder (average particle diameter = 2.5 μm): 80.0 percent
by weight

10 dipentaerythritol hexaacrylate (photosensitive monomer):
14.0 percent by weight

 2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
1.8 percent by weight

 2,4-diethylthioxanthone: 0.9 percent by weight

15 2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
2.1 percent by weight

 di-n-butyl phthalate: 1.2 percent by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste

20 P10 and evaluation of properties>

 The photo-curing depth of the resulting
~~Photosensitive~~photosensitive paste P10 was 14.8 μm at an amount
of exposure of 400 mJ/cm^2 . A film having a thickness of 13.8 μm
was formed on an alumina substrate through screen printing by
25 using this ~~Photosensitive~~photosensitive paste P10. Thereafter,
the resulting film was cured by application of ultraviolet light

under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with ethanol. As a result, the minimum L/S was $25/25 \text{ }\mu\text{m}$.

The aspect ratio of the pattern was determined from
5 dimensions after firing. The resulting aspect ratio was 0.53.

Subsequently, a film having a thickness of $25 \text{ }\mu\text{m}$ was formed on an alumina substrate by using this
~~Photosensitive~~photosensitive paste P10 through screen printing, and the resulting film was cured by application of ultraviolet
10 light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers hardness of this coating film measured 16.9 Hv .

†

Example No. 11†

15 <Preparation of ~~Photosensitive~~photosensitive paste P11>

The following materials were blended and kneaded, so that
~~Photosensitive~~photosensitive paste P11 containing no polymer was prepared.

AgPd powder (average particle diameter = $2.0 \text{ }\mu\text{m}$): 80.0
20 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer):
14.0 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
3.0 percent by weight

25 2,4-diethylthioxanthone: 0.9 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:

2.1 percent by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste P11 and evaluation of properties>

5 The photo-curing depth of the resulting ~~Photosensitive~~photosensitive paste P11 was 14.1 μm at an amount of exposure of 400 mJ/cm^2 . A film having a thickness of 14.0 μm was formed on an alumina substrate through screen printing by using this ~~Photosensitive~~photosensitive paste P11. Thereafter, 10 the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with ethanol. As a result, the minimum L/S was 20/20 μm .

15 The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.70.

Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this ~~Photosensitive~~photosensitive paste P11 through screen printing, and the resulting film was cured by application of ultraviolet 20 light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 15.7 Hv.

†

Example No. 12†

25 <Preparation of ~~Photosensitive~~photosensitive paste P12>

The following materials were blended and kneaded, so that

~~Photosensitive~~photosensitive paste P12 containing no polymer was prepared.

Ag powder (average particle diameter = 3.0 μm): 75.0 percent by weight

5 trimethylolpropane triacrylate (not modified by ethylene oxide) (photosensitive monomer): 16.5 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
5.0 percent by weight

2,4-diethylthioxanthone: 2.0 percent by weight

10 thixotropic agent: 1.5 percent by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste P12 and evaluation of properties>

The photo-curing depth of the resulting

15 ~~Photosensitive~~photosensitive paste P12 was 17.1 μm at an amount of exposure of 400 mJ/cm². A film having a thickness of 17.0 μm was formed on an alumina substrate through screen printing by using this ~~Photosensitive~~photosensitive paste P12. Thereafter, the resulting film was cured by application of ultraviolet light
20 under a condition of 400 mJ/cm² through a photomask, and uncured portions were removed with ethanol. As a result, the minimum L/S was 30/30 μm .

The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.61.

25 Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this

~~Photosensitive~~photosensitive paste P12 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers
5 hardness of this coating film measured 27.5 Hv .

†

Example No. 13†

<Preparation of ~~Photosensitive~~photosensitive paste P13>

The following materials were blended and kneaded, so that
10 ~~Photosensitive~~photosensitive paste P13 containing a polymer within the scope of the present invention was prepared.

Ag powder (average particle diameter = $2.8 \text{ }\mu\text{m}$): 75.0 percent by weight

acrylic copolymer (polymer): 0.5 percent by weight

15 trimethylolpropane EO-modified (degree of polymerization $n =$

1) triacrylate (photosensitive monomer): 14.5 percent by weight

(photosensitive monomer/(photosensitive monomer + polymer) = $14.5/(14.5 + 0.5) = 0.97$)

benzyl dimethyl ketal: 2.0 percent by weight

20 bis(2,4,6-trimethylbenzoyl)-phenylphosphine oxide: 2.0 percent by weight

dipropylene glycol monomethyl ether: 5.0 percent by weight

thixotropic agent: 1.0 percent by weight

25 <Formation of film by using ~~Photosensitive~~photosensitive paste P13 and evaluation of properties>

The photo-curing depth of the resulting
~~Photosensitive~~photosensitive paste P13 was 16.7 μm at an amount
of exposure of 400 mJ/cm^2 . A film having a thickness of 16.5 μm
was formed on an alumina substrate through screen printing by
5 using this ~~Photosensitive~~photosensitive paste P13. Thereafter,
the resulting film was cured by application of ultraviolet light
under a condition of 400 mJ/cm^2 through a photomask, and uncured
portions were removed with ethanol. As a result, the minimum L/S
was 25/25 μm .

10 The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.68.

Subsequently, a film having a thickness of 25 μm was formed
on an alumina substrate by using this
~~Photosensitive~~photosensitive paste P13 through screen printing,
15 and the resulting film was cured by application of ultraviolet
light at 400 mJ/cm^2 . This operation was repeated, so that a
paste film having a thickness of 100 μm was formed. The Vickers
hardness of this coating film measured 19.9 Hv.

†

20 Example No. 14†

<Preparation of ~~Photosensitive~~photosensitive paste P14>

The following materials were blended and kneaded, so that
~~Photosensitive~~photosensitive paste P14 containing a polymer
within the scope of the present invention was prepared.

25 Ag powder (average particle diameter = 2.8 μm): 75.0 percent
by weight

acrylic copolymer (polymer): 1.0 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer):

17.5 percent by weight

(photosensitive monomer/(photosensitive monomer + polymer) =

5 17.5/(17.5 + 1.0) = 0.95)

1-hydroxy-cyclohexyl-phenyl-ketone: 2.5 percent by weight

bis(2,4,6-trimethylbenzoyl)-phenylphosphine oxide: 3.0

percent by weight

dipropylene glycol monomethyl ether: 1.0 percent by weight

10

<Formation of film by using ~~Photosensitive~~photosensitive paste
P14 and evaluation of properties>

The photo-curing depth of the resulting

~~Photosensitive~~photosensitive paste P14 was 16.0 μm at an amount

15 of exposure of 400 mJ/cm^2 . A film having a thickness of 15.8 μm

was formed on an alumina substrate through screen printing by

using this ~~Photosensitive~~photosensitive paste P14. Thereafter,

the resulting film was cured by application of ultraviolet light

under a condition of 400 mJ/cm^2 through a photomask, and uncured

20 portions were removed with ethanol. As a result, the minimum L/S
was 25/25 μm .

The aspect ratio of the pattern was determined from

dimensions after firing. The resulting aspect ratio was 0.62.

Subsequently, a film having a thickness of 25 μm was formed

25 on an alumina substrate by using this

~~Photosensitive~~photosensitive paste P14 through screen printing,

and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers hardness of this coating film measured 18.5 Hv .

5 †

Example No. 15†

<Preparation of ~~Photosensitive~~photosensitive paste P15>

The following materials were blended and kneaded, so that ~~Photosensitive~~photosensitive paste P15 containing a polymer
10 within the scope of the present invention was prepared.

Ag powder (average particle diameter = $2.8 \text{ }\mu\text{m}$): 75.0 percent
by weight

acrylic copolymer (polymer): 1.0 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer): 9.0
15 percent by weight

$(\text{photosensitive monomer} / (\text{photosensitive monomer} + \text{polymer})) =$
 $9.0 / (9.0 + 1.0) = 0.90$

1-hydroxy-cyclohexyl-phenyl-ketone: 3.5 percent by weight

bis(2,4,6-trimethylbenzoyl)-phenylphosphine oxide: 5.5
20 percent by weight

dipropylene glycol monomethyl ether: 4.0 percent by weight

thixotropic agent: 2.0 percent by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste
25 P15 and evaluation of properties>

The photo-curing depth of the resulting

~~Photosensitive~~photosensitive paste P15 was 15.6 μm at an amount of exposure of 400 mJ/cm^2 . A film having a thickness of 15.1 μm was formed on an alumina substrate through screen printing by using this ~~Photosensitive~~photosensitive paste P15. Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with ethanol. As a result, the minimum L/S was 25/25 μm .

The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.60.

Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this ~~Photosensitive~~photosensitive paste P15 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 18.4 Hv.

†

Example No. 16†

<Preparation of ~~Photosensitive~~photosensitive paste P16>

The following materials were blended and kneaded, so that ~~Photosensitive~~photosensitive paste P16 containing a polymer within the scope of the present invention was prepared.

Ag powder (average particle diameter = 2.8 μm): 75.0 percent by weight

acrylic copolymer (polymer): 2.0 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer):

12.5 percent by weight

(photosensitive monomer/(photosensitive monomer + polymer) =

12.5/(12.5 + 2.0) = 0.86)

5 1-hydroxy-cyclohexyl-phenyl-ketone: 2.0 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:

3.2 percent by weight

dipropylene glycol monomethyl ether: 3.8 percent by weight

thixotropic agent: 1.5 percent by weight

10

<Formation of film by using ~~Photosensitive~~photosensitive paste
P16 and evaluation of properties>

The photo-curing depth of the resulting

15 ~~Photosensitive~~photosensitive paste P16 was 14.2 μm at an amount
of exposure of 400 mJ/cm^2 . A film having a thickness of 14.0 μm
was formed on an alumina substrate through screen printing by
using this ~~Photosensitive~~photosensitive paste P16. Thereafter,
the resulting film was cured by application of ultraviolet light
under a condition of 400 mJ/cm^2 through a photomask, and uncured
20 portions were removed with ethanol. As a result, the minimum L/S
was 30/25 μm .

The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.48.

25 Subsequently, a film having a thickness of 25 μm was formed
on an alumina substrate by using this
~~Photosensitive~~photosensitive paste P16 through screen printing,

and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers hardness of this coating film measured 18.0 Hv .

5 †

Example No. 17†

<Preparation of ~~Photosensitive~~photosensitive paste P17>

The following materials were blended and kneaded, so that ~~Photosensitive~~photosensitive paste P17 containing no polymer was
10 prepared.

Ag powder (average particle diameter = $3.0 \text{ }\mu\text{m}$): 75.0 percent by weight

trimethylolpropane EO-modified (degree of polymerization $n = 1$) triacrylate (photosensitive monomer): 16.0 percent by weight
15 2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
4.5 percent by weight

2,4-diethylthioxanthone: 1.0 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
1.5 percent by weight

20 thixotropic agent: 2.0 percent by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste P17 and evaluation of properties>

The photo-curing depth of the resulting
25 ~~Photosensitive~~photosensitive paste P17 was $12.5 \text{ }\mu\text{m}$ at an amount of exposure of 400 mJ/cm^2 . A film having a thickness of $11.5 \text{ }\mu\text{m}$

was formed on an alumina substrate through screen printing by using this ~~Photosensitive~~photosensitive paste P17. Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with ethanol. As a result, the minimum L/S was 30/25 μm .

The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.55.

Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this ~~Photosensitive~~photosensitive paste P17 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 15.8 Hv.

†

Example No. 18†

<Preparation of ~~Photosensitive~~photosensitive paste P18>

The following materials were blended and kneaded, so that ~~Photosensitive~~photosensitive paste P18 containing no polymer was prepared.

Ag powder (average particle diameter = 3.0 μm): 75.0 percent by weight

triallyl isocyanurate (photosensitive monomer): 17.5 percent by weight

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:

2.5 percent by weight

2,4-diethylthioxanthone: 0.9 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:

2.5 percent by weight

5 thixotropic agent: 1.6 percent by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste
P18 and evaluation of properties>

10 The photo-curing depth of the resulting
~~Photosensitive~~photosensitive paste P18 was 13.8 μm at an amount
of exposure of 400 mJ/cm^2 . A film having a thickness of 12.5 μm
was formed on an alumina substrate through screen printing by
using this ~~Photosensitive~~photosensitive paste P18. Thereafter,
the resulting film was cured by application of ultraviolet light
15 under a condition of 400 mJ/cm^2 through a photomask, and uncured
portions were removed with ethanol. As a result, the minimum L/S
was 35/35 μm .

 The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.35.

20 Subsequently, a film having a thickness of 25 μm was formed
on an alumina substrate by using this
~~Photosensitive~~photosensitive paste P18 through screen printing,
and the resulting film was cured by application of ultraviolet
light at 400 mJ/cm^2 . This operation was repeated, so that a
25 paste film having a thickness of 100 μm was formed. The Vickers
hardness of this coating film measured 14.3 Hv.

†

Example No. 19†

<Preparation of ~~Photosensitive~~photosensitive paste P19>

The following materials were blended and kneaded, so that
5 ~~Photosensitive~~photosensitive paste P19 containing no polymer was prepared.

Ag powder (average particle diameter = 3.0 μm): 75.0 percent by weight

trimethylolpropane EO-modified (degree of polymerization n =
10 3) triacrylate (photosensitive monomer): 18.0 percent by weight
benzyl dimethyl ketal: 2.5 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
2.5 percent by weight

thixotropic agent: 2.0 percent by weight

15

<Formation of film by using ~~Photosensitive~~photosensitive paste P19 and evaluation of properties>

The photo-curing depth of the resulting
~~Photosensitive~~photosensitive paste P19 was 11.3 μm at an amount
20 of exposure of 400 mJ/cm². A film having a thickness of 10.0 μm was formed on an alumina substrate through screen printing by using this ~~Photosensitive~~photosensitive paste P19. Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm² through a photomask, and uncured
25 portions were removed with ethanol. As a result, the minimum L/S was 35/30 μm .

The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.30.

Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this

5 ~~Photosensitive~~photosensitive paste P19 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm². This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 13.2 Hv.

10 †

Example No. 20†

<Preparation of ~~Photosensitive~~photosensitive paste P20>

The following materials were blended and kneaded, so that ~~Photosensitive~~photosensitive paste P20 containing no polymer was
15 prepared.

Ag powder (average particle diameter = 3.0 μm): 75.0 percent by weight

trimethylolpropane EO-modified (degree of polymerization n = 4) triacrylate (photosensitive monomer): 18.5 percent by weight

20 2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
2.5 percent by weight

2,4-diethylthioxanthone: 0.9 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
1.6 percent by weight

25 thixotropic agent: 1.5 percent by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste P20 and evaluation of properties>

The photo-curing depth of the resulting ~~Photosensitive~~photosensitive paste P20 was 11.0 μm at an amount of exposure of 400 mJ/cm^2 . A film having a thickness of 9.5 μm was formed on an alumina substrate through screen printing by using this ~~Photosensitive~~photosensitive paste P20. Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with ethanol. As a result, the minimum L/S was 40/30 μm .

The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.29.

Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this ~~Photosensitive~~photosensitive paste P20 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 13.1 Hv.

†

Example No. 21†

<Preparation of ~~Photosensitive~~photosensitive paste P21>

The following materials were blended and kneaded, so that ~~Photosensitive~~photosensitive paste P21 containing no polymer was prepared.

Ag powder (average particle diameter = 2.8 μm): 80.0 percent
by weight

dipentaerythritol hexaacrylate (photosensitive monomer):
13.2 percent by weight

5 2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
2.0 percent by weight

2,4-diethylthioxanthone: 0.9 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
2.3 percent by weight

10 ultraviolet absorber (anthraquinone based dye): 1.6 percent
by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste
P21 and evaluation of properties>

15 The photo-curing depth of the resulting
~~Photosensitive~~photosensitive paste P21 was 15.5 μm at an amount
of exposure of 400 mJ/cm^2 . A film having a thickness of 14.8 μm
was formed on an alumina substrate through screen printing by
using this ~~Photosensitive~~photosensitive paste P21. Thereafter,
20 the resulting film was cured by application of ultraviolet light
under a condition of 400 mJ/cm^2 through a photomask, and uncured
portions were removed with ethanol. As a result, the minimum L/S
was 25/20 μm .

The aspect ratio of the pattern was determined from
25 dimensions after firing. The resulting aspect ratio was 0.65.

Subsequently, a film having a thickness of 25 μm was formed

on an alumina substrate by using this
~~Photosensitive~~photosensitive paste P21 through screen printing,
and the resulting film was cured by application of ultraviolet
light at 400 mJ/cm^2 . This operation was repeated, so that a
5 paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers
hardness of this coating film measured 15.1 Hv.

†

Comparative ~~example~~Example No. 1†

<Preparation of ~~Photosensitive~~photosensitive paste P01>

10 The following materials were blended and kneaded, so that
~~Photosensitive~~photosensitive paste P01 containing a polymer
~~exceeding~~outside of the scope of the present invention was
prepared.

Ag powder (average particle diameter = $2.8 \text{ }\mu\text{m}$): 75.0 percent
15 by weight

acrylic copolymer (polymer): 3.0 percent by weight

dipentaerythritol hexaacrylate (photosensitive monomer):
13.0 percent by weight

(photosensitive monomer/(photosensitive monomer + polymer) =
20 $13.0 / (13.0 + 3.0) = 0.81$)

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
2.0 percent by weight

2,4-diethylthioxanthone: 0.5 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
25 3.0 percent by weight

dipropylene glycol monomethyl ether: 2.0 percent by weight

thixotropic agent: 1.5 percent by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste P01 and evaluation of properties>

The photo-curing depth of the resulting
5 ~~Photosensitive~~photosensitive paste P01 was 9.6 μm at an amount of exposure of 400 mJ/cm^2 . A film having a thickness of 9.6 μm was formed on an alumina substrate through screen printing by using this ~~Photosensitive~~photosensitive paste P01. Thereafter, the resulting film was cured by application of ultraviolet light
10 under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with ethanol. As a result, the minimum L/S was 30/30 μm .

The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.32.

15 Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this ~~Photosensitive~~photosensitive paste P01 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a
20 paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 17.3 Hv.

†

Comparative ~~example~~Example No. 2†

<Preparation of ~~Photosensitive~~photosensitive paste P02>

25 The following materials were blended and kneaded, so that ~~Photosensitive~~photosensitive paste P02 containing a polymer

~~exceeding~~outside of the scope of the present invention was prepared.

Ag powder (average particle diameter = 2.8 μm): 75.0 percent by weight

5 acrylic copolymer (polymer): 4.0 percent by weight

dipentaerythritol hydroxypentaacrylate (photosensitive monomer): 11.5 percent by weight

(photosensitive monomer/(photosensitive monomer + polymer) = 11.5/(11.5 + 4.0) = 0.74)

10 2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
2.5 percent by weight

2,4-diethylthioxanthone: 0.5 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
1.0 percent by weight

15 dipropylene glycol monomethyl ether: 3.5 percent by weight

thixotropic agent: 2.0 percent by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste

20 P02 and evaluation of properties>

The photo-curing depth of the resulting ~~Photosensitive~~photosensitive paste P02 was 6.7 μm at an amount of exposure of 400 mJ/cm². A film having a thickness of 6.7 μm was formed on an alumina substrate through screen printing by using
25 this ~~Photosensitive~~photosensitive paste P02. Thereafter, the resulting film was cured by application of ultraviolet light

under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with a 0.5 percent by weight sodium carbonate aqueous solution. As a result, the minimum L/S was $30/30 \text{ }\mu\text{m}$.

5 The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.27.

Subsequently, a film having a thickness of $25 \text{ }\mu\text{m}$ was formed on an alumina substrate by using this ~~Photosensitive~~photosensitive paste P02 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers hardness of this coating film measured 15.4 Hv .

+

15 Comparative ~~example~~Example No. 3+

<Preparation of ~~Photosensitive~~photosensitive paste P03>

The following materials were blended and kneaded, so that ~~Photosensitive~~photosensitive paste P03 containing a polymer ~~exceeding~~outside of the scope of the present invention was prepared.

Ag powder (average particle diameter = $2.8 \text{ }\mu\text{m}$): 74.0 percent by weight

acrylic polymer (polymer): 6.2 percent by weight

trimethylolpropane EO-modified (degree of polymerization $n =$

25 1) triacrylate (photosensitive monomer): 6.0 percent by weight

(photosensitive monomer/(photosensitive monomer + polymer) =

$$6.0 / (6.0 + 6.2) = 0.49)$$

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:

0.6 percent by weight

2,4-diethylthioxanthone: 0.2 percent by weight

5 2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:

0.9 percent by weight

dipropylene glycol monomethyl ether: 11.6 percent by weight

thixotropic agent: 0.5 percent by weight

10 <Formation of film by using ~~Photosensitive~~photosensitive paste
P03 and evaluation of properties>

The photo-curing depth of the resulting
~~Photosensitive~~photosensitive paste P03 was 9.1 μm at an amount of
exposure of 400 mJ/cm^2 . A film having a thickness of 8.5 μm was
15 formed on an alumina substrate through screen printing by using
this ~~Photosensitive~~photosensitive paste P03. Thereafter, the
resulting film was cured by application of ultraviolet light
under a condition of 400 mJ/cm^2 through a photomask, and uncured
portions were removed with a 0.5 percent by weight sodium
20 carbonate aqueous solution. As a result, the minimum L/S was
25/25 μm .

The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.43.

Subsequently, a film having a thickness of 25 μm was formed
25 on an alumina substrate by using this
~~Photosensitive~~photosensitive paste P03 through screen printing,

and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers hardness of this coating film measured 18.8 Hv .

5 †

Comparative ~~example~~ Example No. 4†

<Preparation of ~~Photosensitive~~ photosensitive paste P04>

The following materials were blended and kneaded, so that ~~Photosensitive~~ photosensitive paste P04 containing a polymer
10 ~~exceeding~~ outside of the scope of the present invention was prepared.

Ag powder (average particle diameter = $2.8 \text{ }\mu\text{m}$): 77.0 percent by weight

acrylic polymer (polymer): 5.5 percent by weight

15 trimethylolpropane EO-modified (degree of polymerization $n =$

1) triacrylate (photosensitive monomer): 6.2 percent by weight

(photosensitive monomer/(photosensitive monomer + polymer) = $6.2/(6.2 + 5.5) = 0.53$)

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
20 1.0 percent by weight

2,4-diethylthioxanthone: 0.2 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
0.4 percent by weight

pentamethylene glycol: 1.2 percent by weight

25 dipropylene glycol monomethyl ether: 8.5 percent by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste P04 and evaluation of properties>

The photo-curing depth of the resulting ~~Photosensitive~~photosensitive paste P04 was 7.2 μm at an amount of exposure of 400 mJ/cm^2 . A film having a thickness of 7.0 μm was formed on an alumina substrate through screen printing by using this ~~Photosensitive~~photosensitive paste P04. Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with a 0.5 percent by weight sodium carbonate aqueous solution. As a result, the minimum L/S was 30/25 μm .

The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.31.

Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this ~~Photosensitive~~photosensitive paste P04 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 12.7 Hv.

†

Comparative example No. 5†

<Preparation of ~~Photosensitive~~photosensitive paste P05>

The following materials were blended and kneaded, so that ~~Photosensitive~~photosensitive paste P05 containing a polymer

~~exceeding~~outside of the scope of the present invention was prepared.

Ag powder (average particle diameter = 2.8 μm): 80 percent by weight

5 Si-B based glass powder (average particle diameter = 1.5 μm): 2.4 percent by weight

acrylic polymer (polymer): 4.1 percent by weight

trimethylolpropane EO-modified (degree of polymerization n = 1) triacrylate (photosensitive monomer): 2.8 percent by weight

10 (photosensitive monomer/(photosensitive monomer + polymer) = $2.8/(2.8 + 4.1) = 0.41$)

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on: 1.8 percent by weight

2,4-diethylthioxanthone: 0.3 percent by weight

15 2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1: 1.1 percent by weight

ethylcarbitol acetate: 7.5 percent by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste

20 P05 and evaluation of properties>

The photo-curing depth of the resulting ~~Photosensitive~~photosensitive paste P05 was 7.0 μm at an amount of exposure of 400 mJ/cm². A film having a thickness of 7.0 μm was formed on a PET film through screen printing by using this

25 ~~Photosensitive~~photosensitive paste P05. Thereafter, the resulting film was cured by application of ultraviolet light

under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with a 0.5 percent by weight sodium carbonate aqueous solution. As a result, the minimum L/S was $30/30 \text{ }\mu\text{m}$.

5 Subsequently, the pattern disposed on this PET film was turned upside down, and was pressed and transferred to a green sheet by using a thermocompression bonding device under the condition of 60°C , 0.5 MPa , and 60 seconds. The resulting pattern was fired and the width and the thickness of the pattern
10 were observed with a laser microscope. The resulting aspect ratio was 0.33.

 A film having a thickness of $25 \text{ }\mu\text{m}$ was formed on an alumina substrate by using this ~~Photosensitive~~photosensitive paste P05 through screen printing, and the resulting film was cured by
15 application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of $100 \text{ }\mu\text{m}$ was formed. The Vickers hardness of this coating film measured 8.1 Hv .

†

20 Comparative ~~example~~Example No. 6†

<Preparation of ~~Photosensitive~~photosensitive paste P06>

 The following materials were blended and kneaded, so that ~~Photosensitive~~photosensitive paste P06 containing a polymer
 ~~exceeding~~outside of the scope of the present invention was
25 prepared.

 Cu powder (average particle diameter = $2.5 \text{ }\mu\text{m}$): 80 percent

by weight

acrylic polymer (polymer): 5.6 percent by weight

trimethylolpropane EO-modified (degree of polymerization n =

1) triacrylate (photosensitive monomer): 3.8 percent by weight

5 (photosensitive monomer/(photosensitive monomer + polymer) =
3.8/(3.8 + 5.6) = 0.40)

2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:

1.0 percent by weight

2,4-diethylthioxanthone: 0.3 percent by weight

10 2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
1.6 percent by weight

dipropylene glycol monomethyl ether: 6.9 percent by weight

dibutyl phthalate: 0.8 percent by weight

15 <Formation of film by using ~~Photosensitive~~photosensitive paste
P06 and evaluation of properties>

The photo-curing depth of the resulting
~~Photosensitive~~photosensitive paste P06 was 7.9 μm at an amount of
exposure of 400 mJ/cm^2 . A film having a thickness of 7.1 μm was
20 formed on a PET film through screen printing by using this
~~Photosensitive~~photosensitive paste P06. Thereafter, the
resulting film was cured by application of ultraviolet light
under a condition of 400 mJ/cm^2 through a photomask, and uncured
portions were removed with a 0.5 percent by weight sodium
25 carbonate aqueous solution. As a result, the minimum L/S was
30/30 μm .

Subsequently, the pattern disposed on this PET film was turned upside down, and was pressed and transferred to a green sheet by using a thermocompression bonding device under the condition of 60°C, 0.5 MPa, and 60 seconds. The resulting pattern was fired and the width and the thickness of the pattern were observed with a laser microscope. The resulting aspect ratio was 0.20.

A film having a thickness of 25 μm was formed on an alumina substrate by using this ~~Photosensitive~~photosensitive paste P06 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm². This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 12.7 Hv.

Comparative ~~example~~Example No. 7†

<Preparation of ~~Photosensitive~~photosensitive paste P07>

The following materials were blended and kneaded, so that ~~Photosensitive~~photosensitive paste P07 containing a polymer ~~exceeding~~outside of the scope of the present invention was prepared.

Cu powder (average particle diameter = 2.5 μm): 80 percent by weight

Si-B based glass powder (average particle diameter = 1.5 μm): 0.4 percent by weight

acrylic polymer (polymer): 7.8 percent by weight

trimethylolpropane EO-modified (degree of polymerization $n =$
1) triacrylate (photosensitive monomer): 2.8 percent by weight
(photosensitive monomer/(photosensitive monomer + polymer) =
2.8/(2.8 + 7.8) = 0.26)

5 2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
1.0 percent by weight 2,4-diethylthioxanthone: 0.3 percent by
weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
0.5 percent by weight

10 dipropylene glycol monomethyl ether: 7.2 percent by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste
P07 and evaluation of properties>

The photo-curing depth of the resulting
15 ~~Photosensitive~~photosensitive paste P07 was 7.0 μm at an amount of
exposure of 400 mJ/cm^2 . A film having a thickness of 7.0 μm was
formed on an alumina substrate through screen printing by using
this ~~Photosensitive~~photosensitive paste P07. Thereafter, the
resulting film was cured by application of ultraviolet light
20 under a condition of 400 mJ/cm^2 through a photomask, and uncured
portions were removed with acetone. As a result, the minimum L/S
was 35/30 μm .

The aspect ratio of the pattern was determined from
dimensions after firing. The resulting aspect ratio was 0.27.

25 Subsequently, a film having a thickness of 25 μm was formed
on an alumina substrate by using this

~~Photosensitive~~photosensitive paste P07 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm². This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers
5 hardness of this coating film measured 10.5 Hv.

†

Comparative ~~example~~Example No. 8†

<Preparation of ~~Photosensitive~~photosensitive paste P08>

The following materials were blended and kneaded, so that
10 ~~Photosensitive~~photosensitive paste P08 containing a polymer
~~exceeding~~outside of the scope of the present invention was prepared.

AgPd powder (average particle diameter = 2.0 μm): 75 percent
by weight

15 acrylic polymer (polymer): 6.8 percent by weight

trimethylolpropane EO-modified (degree of polymerization n =
1) triacrylate (photosensitive monomer): 4.1 percent by weight
(photosensitive monomer/(photosensitive monomer + polymer) =
4.1/(4.1 + 6.8) = 0.38)

20 2-methyl-1[4-(methylthio)phenyl]-2-morpholinopropane-1-on:
1.5 percent by weight

2,4-diethylthioxanthone: 0.3 percent by weight

2-benzyl-2-dimethylamino-1-(4-morpholinophenyl)-butanone-1:
1.1 percent by weight

25 dipropylene glycol monomethyl ether: 11.2 percent by weight

<Formation of film by using ~~Photosensitive~~photosensitive paste P08 and evaluation of properties>

The photo-curing depth of the resulting ~~Photosensitive~~photosensitive paste P08 was 6.5 μm at an amount of exposure of 400 mJ/cm^2 . A film having a thickness of 6.5 μm was formed on an alumina substrate through screen printing by using this ~~Photosensitive~~photosensitive paste P08. Thereafter, the resulting film was cured by application of ultraviolet light under a condition of 400 mJ/cm^2 through a photomask, and uncured portions were removed with a 0.5 percent by weight sodium carbonate aqueous solution. As a result, the minimum L/S was 25/25 μm .

The aspect ratio of the pattern was determined from dimensions after firing. The resulting aspect ratio was 0.41.

Subsequently, a film having a thickness of 25 μm was formed on an alumina substrate by using this ~~Photosensitive~~photosensitive paste P08 through screen printing, and the resulting film was cured by application of ultraviolet light at 400 mJ/cm^2 . This operation was repeated, so that a paste film having a thickness of 100 μm was formed. The Vickers hardness of this coating film measured 13.6 Hv.

The conditions, various properties, and the like of Example Nos. 1 to 21 measured as described above are shown in Tables 1 to 5, and the conditions, various properties, and the like of Comparative example Nos. 1 to 8 are shown in Tables 6 and 7.

{Table 1}

Example No.	Example No. 1	Example No. 2	Example No. 3	Example No. 4
Paste	P1	P2	P3	P4
Inorganic powder 1	Ag	Ag	Ag	Ag
Inorganic powder 2	-	-	-	-
Inorganic powder 1 particle diameter (μm)	2.8	2.8	2.8	2.8
Inorganic powder 2 particle diameter (μm)	-	-	-	-
Inorganic powder content (percent by weight)	75.0	80.0	85.0	71.0
Photo-curing depth (at 400 mJ/cm^2) (μm)	18.9	16.2	12.8	22.1
Vickers hardness (HV)	24.6	15.2	10.6	30.2
Resolution (L/S)	20/20	25/25	25/25	25/20
Aspect ratio after firing	0.80	0.69	0.61	0.68
Formation object (substrate/film)	alumina	alumina	alumina	alumina
Method for forming thick film pattern	screen printing	screen printing	screen printing	screen printing
Monomer 1	A	A	A	A
Monomer 2	-	-	-	B
Degree of polymerization of ethylene oxide structure	0	0	0	1
Double bond concentration of photosensitive monomer ($\text{mmol}\cdot\text{g}^{-1}$)	10.38	10.38	10.38	8.70
Amount of polymer (percent by weight)	0	0	0	0
Monomer/ (monomer + polymer)	1.0	1.0	1.0	1.0
Organic solvent	PMG	-	ECA	-
Amount of solvent (percent by weight)	3.0	0	1.3	0
Development solution	ethanol	ethanol	ethanol	acetone
Various additives	-	-	-	thixotropic agent
Drying step	needless	needless	needless	needless

{Table 2}

Example No.	Example No. 5	Example No. 6	Example No. 7	Example No. 8
Paste	P5	P6	P7	P8
Inorganic powder 1	Ag	Ag	Ag	Ag and Al ₂ O ₃ -coated Ag
Inorganic powder 2	-	-	glass	glass
Inorganic powder 1 particle diameter (μm)	2.8	2.8	2.8	2.8/2.0
Inorganic powder 2 particle diameter (μm)	-	-	1.5	1.5
Inorganic powder content (percent by weight)	75.0	80.0	80.0/2.4	56.3/18.8/2.4
Photo-curing depth (at 400 mJ/cm ²) (μm)	18.5	17.0	15.2	13.9
Vickers hardness (HV)	26.5	17.1	14.8	15.4
Resolution (L/S)	25/25	30/30	25/30	25/30
Aspect ratio after firing	0.62	0.55	0.51	0.45
Formation object (substrate/film)	alumina	alumina	PET	PET
Method for forming thick film pattern	screen printing	screen printing	screen printing	screen printing
Monomer 1	A	A	A	A
Monomer 2	B	B	-	-
Degree of polymerization of ethylene oxide structure	1	1	0	0
Double bond concentration of photosensitive monomer (mmol·g ⁻¹)	8.70	8.70	10.38	10.38
Amount of polymer (percent by weight)	0	0	0	0
Monomer/ (monomer + polymer)	1.0	1.0	1.0	1.0
Organic solvent	-	PMG	-	DGME
Amount of solvent (percent by weight)	0	0.7	0	1.3
Development solution	acetone	acetone	ethanol	ethanol
Various additives	-	-	-	-
Drying step	needless	needless	needless	needless

{Table 3}

Example No.	Example No. 9	Example No. 10	Example No. 11	Example No. 12
Paste	P9	P10	P11	P12
Inorganic powder 1	Cu	Cu	AgPd	Ag
Inorganic powder 2	-	-	-	-
Inorganic powder 1 particle diameter (μm)	2.5	2.5	2.0	3.0
Inorganic powder 2 particle diameter (μm)	-	-	-	-
Inorganic powder content (percent by weight)	77.0	80.0	80.0	75.0
Photo-curing depth (at 400 mJ/cm^2) (μm)	15.8	14.8	14.1	17.1
Vickers hardness (HV)	17.8	16.9	15.7	27.5
Resolution (L/S)	30/30	25/25	20/20	30/30
Aspect ratio after firing	0.59	0.53	0.7	0.61
Formation object (substrate/film)	alumina	alumina	alumina	alumina
Method for forming thick film pattern	screen printing	screen printing	screen printing	screen printing
Monomer 1	A	A	A	C
Monomer 2	-	-	-	-
Degree of polymerization of ethylene oxide structure	0	0	0	0
Double bond concentration of photosensitive monomer ($\text{mmol}\cdot\text{g}^{-1}$)	10.38	10.38	10.38	10.14
Amount of polymer (percent by weight)	0	0	0	0
Monomer/ (monomer + polymer)	1.0	1.0	1.0	1.0
Organic solvent	DGME/PMG	-	-	-
Amount of solvent (percent by weight)	6.0	0	0	0
Development solution	ethanol	ethanol	ethanol	ethanol
Various additives	-	DBP	-	thixotropic agent
Drying step	need	needless	needless	needless

{Table 4}

Example No.	Example No. 13	Example No. 14	Example No. 15	Example No. 16
Paste	P13	P14	P15	P16
Inorganic powder 1	Ag	Ag	Ag	Ag
Inorganic powder 2	-	-	-	-
Inorganic powder 1 particle diameter (μm)	2.8	2.8	2.8	2.8
Inorganic powder 2 particle diameter (μm)	-	-	-	-
Inorganic powder content (percent by weight)	75.0	75.0	75.0	75.0
Photo-curing depth (at 400 mJ/cm^2) (μm)	16.7	16.0	15.6	14.2
Vickers hardness (HV)	19.9	18.5	18.4	18.0
Resolution (L/S)	25/25	25/25	25/25	30/25
Aspect ratio after firing	0.68	0.62	0.60	0.48
Formation object (substrate/film)	alumina	alumina	alumina	alumina
Method for forming thick film pattern	screen printing	screen printing	screen printing	screen printing
Monomer 1	B	A	A	A
Monomer 2	-	-	-	-
Degree of polymerization of ethylene oxide structure	1	0	0	0
Double bond concentration of photosensitive monomer ($\text{mmol}\cdot\text{g}^{-1}$)	10.38	10.38	10.38	10.38
Amount of polymer (percent by weight)	0.5	1.0	1.0	2.0
Monomer/ (monomer + polymer)	0.97	0.95	0.90	0.86
Organic solvent	DGME	DGME	DGME	DGME
Amount of solvent (percent by weight)	5.0	1.0	4.0	3.8
Development solution	ethanol	ethanol	ethanol	ethanol
Various additives	thixotropic agent	-	thixotropic agent	thixotropic agent
Drying step	needless	needless	needless	needless

{Table 5}

Example No.	Example No. 17	Example No. 18	Example No. 19	Example No. 20	Example No. 21
Paste	P17	P18	P19	P20	P21
Inorganic powder 1	Ag	Ag	Ag	Ag	Ag
Inorganic powder 2	-	-	-	-	-
Inorganic powder 1 particle diameter (μm)	3.0	3.0	3.0	3.0	2.8
Inorganic powder 2 particle diameter (μm)	-	-	-	-	-
Inorganic powder content (percent by weight)	75.0	75.0	75.0	75.0	80.0
Photo-curing depth (at 400 mJ/cm^2) (μm)	12.5	13.8	11.3	11.0	15.5
Vickers hardness (HV)	15.8	14.3	13.2	13.1	15.1
Resolution (L/S)	30/25	35/35	35/30	40/30	25/20
Aspect ratio after firing	0.55	0.35	0.30	0.29	0.65
Formation object (substrate/film)	alumina	alumina	alumina	alumina	alumina
Method for forming thick film pattern	screen printing	screen printing	screen printing	screen printing	screen printing
Monomer 1	B	D	B	B	A
Monomer 2	-	-	-	-	-
Degree of polymerization of ethylene oxide structure	1	0	3	4	0
Double bond concentration of photosensitive monomer ($\text{mmol}\cdot\text{g}^{-1}$)	7.01	12.05	4.34	3.64	10.38
Amount of polymer (percent by weight)	0	0	0	0	0
Monomer/ (monomer + polymer)	1.0	1.0	1.0	1.0	1.0
Organic solvent	-	-	-	-	-
Amount of solvent (percent by weight)	0	0	0	0	0
Development solution	ethanol	ethanol	ethanol	ethanol	ethanol
Various additives	thixo-tropic agent	thixo-tropic agent	thixo-tropic agent	thixo-tropic agent	ultra-violet absorber
Drying step	needless	needless	needless	needless	needless

{Table 6}

Example No.	Comparative example No. 1	Comparative example No. 2	Comparative example No. 3	Comparative example No. 4
Paste	P01	P02	P03	P04
Inorganic powder 1	Ag	Ag	Ag	Ag
Inorganic powder 2	-	-	-	-
Inorganic powder 1 particle diameter (μm)	2.8	2.8	2.8	2.8
Inorganic powder 2 particle diameter (μm)	-	-	-	-
Inorganic powder content (percent by weight)	75.0	75.0	74.0	77.0
Photo-curing depth (at 400 mJ/cm ²) (μm)	9.6	6.7	9.1	7.2
Vickers hardness (HV)	17.3	15.4	18.8	12.7
Resolution (L/S)	30/30	30/30	25/25	30/25
Aspect ratio after firing	0.32	0.27	0.43	0.31
Formation object (substrate/film)	alumina	alumina	alumina	alumina
Method for forming thick film pattern	screen printing	screen printing	screen printing	screen printing
Monomer 1	A	A	B	B
Monomer 2	-	-	-	-
Degree of polymerization of ethylene oxide structure	0	0	1	1
Double bond concentration of photosensitive monomer (mmol·g ⁻¹)	10.38	10.38	7.01	7.01
Amount of polymer (percent by weight)	3.0	4.0	6.2	5.5
Monomer/ (monomer + polymer)	0.81	0.74	0.49	0.53
Organic solvent	DGME	DGME	DGME	PMG/DGME
Amount of solvent (percent by weight)	2.0	3.5	11.6	1.2/8.5
Development solution	ethanol	sodium carbonate	sodium carbonate	sodium carbonate
Various additives	thixotro- pic agent	thixotro- pic agent	thixotro- pic agent	-
Drying step	needless	needless	need	need

{Table 7}

Example No.	Comparative example No. 5	Comparative example No. 6	Comparative example No. 7	Comparative example No. 8
Paste	P05	P06	P07	P08
Inorganic powder 1	Ag	Cu	Cu	AgPd
Inorganic powder 2	glass powder	-	glass powder	-
Inorganic powder 1 particle diameter (μm)	2.8	2.5	2.5	2.0
Inorganic powder 2 particle diameter (μm)	1.5	-	1.5	-
Inorganic powder content (percent by weight)	80.0/2.4	80.0	80.0/0.4	75.0
Photo-curing depth (at 400 mJ/cm^2) (μm)	7.0	7.9	7.0	6.5
Vickers hardness (HV)	8.1	12.7	10.5	13.6
Resolution (L/S)	30/30	30/30	35/30	25/25
Aspect ratio after firing	0.33	0.20	0.27	0.41
Formation object (substrate/film)	PET	PET	alumina	alumina
Method for forming thick film pattern	screen printing	screen printing	screen printing	screen printing
Monomer 1	B	B	B	B
Monomer 2	-	-	-	-
Degree of polymerization of ethylene oxide structure	1	1	1	1
Double bond concentration of photosensitive monomer ($\text{mmol} \cdot \text{g}^{-1}$)	7.01	7.01	7.01	7.01
Amount of polymer (percent by weight)	4.1	5.6	7.8	6.8
Monomer/ (monomer + polymer)	0.41	0.40	0.26	0.38
Organic solvent	ECA	DGME	DGME	DGME
Amount of solvent (percent by weight)	7.5	6.9	7.2	11.2
Development solution	sodium carbonate	sodium carbonate	acetone	sodium carbonate
Various additives	-	DBP	-	-
Drying step	need	need	need	need

In Tables 1 to 7, monomer A, monomer B, monomer C, monomer D, PMG, ECA, DGME, DBP, and polymer denote the following respective substances.

monomer A: dipentaerythritol hexaacrylate

monomer B: trimethylolpropane EO-modified triacrylate

monomer C: trimethylolpropane triacrylate

monomer D: triallyl isocyanurate

5 PMG: pentamethylene glycol

ECA: ethylcarbitol acetate

DGME: dipropylene glycol monomethyl ether

DBP: dibutyl phthalate

polymer: methacrylic acid-methyl methacrylate copolymer

10 molecular weight $M_w = 15,000$

As is clear from the above-described Example Nos. 1 to 21 and Comparative ~~example~~Example Nos. 1 to 8, the photosensitive paste containing no polymer and the photosensitive paste containing a polymer within the scope of the present invention exhibit photo-curing depths of about 10 μm or more, and thick film patterns having large thicknesses and exhibiting high dimension precision and high shape precision can be formed efficiently by using the photosensitive pastes within the scope of the present invention, although the photosensitive pastes of Comparative ~~example~~Example Nos. 1 to 8 containing a polymer ~~exceeding~~outside of the scope of the present invention exhibit photo-curing depths of less than 10 μm , so that a pattern having an adequate thickness cannot be formed by using such a photosensitive paste.

25 In each of the above-described Examples and Comparative examples, the exposure treatment is conducted through the

photomask. However, it is also possible to apply laser light or UV light with a wavelength of about 300 nm to about 420 nm to a photosensitive paste film by using Maskless Exposure System (produced by Ball semiconductor Inc., for example), so as to cure the photosensitive paste film. In that case, a desired pattern can be formed by moving a stage indicating the photosensitive paste film in accordance with the pattern information input beforehand.

~~SECOND EMBODIMENT~~

Fig. 3 is a sectional view showing an electronic component (ceramic multilayer substrate) according to ~~an~~ another preferred embodiment of the present invention. This ceramic multilayer substrate is preferably a ceramic multilayer substrate provided with electrodes (inner layer copper pattern, surface layer copper pattern, and the like) composed of thick film patterns formed by using the photosensitive paste (photosensitive copper paste) of various preferred embodiments of the present invention.

A ceramic multilayer substrate 11 in the present preferred embodiment is preferably formed by laminating insulator layers 12a, 12b, 12c, 12d, 12e, and 12f and dielectric layers 13a and 13b. In the inside thereof, capacitor patterns, coil patterns, strip lines, and the like are formed from inner layer copper patterns 15 and via holes 16.

Furthermore, a chip component 20, e.g., a chip capacitor, a thick film resistor 21, a semiconductor IC 22, and the like are disposed on one main surface of the ceramic multilayer substrate

11, and are connected to their respective surface layer copper patterns 17 or inner layer copper patterns 15.

In this ceramic multilayer substrate 11, the inner layer copper patterns (thick film patterns) 15 and surface layer copper patterns (thick film patterns) 17 have widths of about 50 μm and film thicknesses of about 5 μm or more.

A method for manufacturing this ceramic multilayer substrate 11 will be described below.

A glass powder, a ceramic powder, and an organic vehicle are mixed, so that an insulator ceramic green sheet slurry is prepared. Likewise, a dielectric ceramic green sheet slurry is prepared. Each of the resulting slurries is molded into the shape of a sheet by a doctor blade method or the like, and is dried at a temperature of about 50°C to about 150°C, so that insulator ceramic green sheets and dielectric ceramic green sheets are produced. The ceramic green sheets are provided with their respective via holes as needed.

A photosensitive paste (photosensitive copper paste) according to ~~ana~~ a preferred embodiment of the present invention, the paste having a predetermined photo-curing depth, is prepared. The photosensitive copper paste is applied to a support to form a photosensitive copper paste film. The film thickness of the photosensitive copper paste film is set in consideration of the photo-curing depth.

This photosensitive copper paste film is subjected to an exposure treatment and, thereafter, is developed, so that a thick

film pattern having a predetermined shape is formed on the support.

The thick film pattern formed on the support is transferred to the ceramic green sheet (insulator ceramic green sheet or
5 dielectric ceramic green sheet (an object to which the transfer is conducted)) produced as described above, so that a capacitor pattern, a coil pattern, or the like is formed.

The ceramic green sheets provided with thick film patterns are stacked, press-bonded and, thereafter, fired at a
10 predetermined temperature. Subsequently, chip components, semiconductor ICs, and the like are mounted, thick film resistors are printed and, thereby, the ceramic multilayer substrate 11 as shown in Fig. 3 is formed.

In the production of this ceramic multilayer substrate 11,
15 since the thick film patterns (inner layer copper patterns, surface layer copper patterns, and the like) are formed by the method for forming a thick film pattern according to various preferred embodiments of the present invention, it becomes possible to form a highly precise, fine thick film pattern having
20 a large film thickness on a ceramic green sheet by a transfer method. Consequently, a ceramic multilayer substrate satisfactorily suitable for an increase in signal speed and an increase in wiring density can be produced efficiently by stacking and press-bonding ceramic green sheets provided with the
25 above-described thick film patterns and, thereafter, firing them at a predetermined temperature.

In the above-described ~~second~~present preferred embodiment, the ceramic multilayer substrate is preferably shown as the electronic component. However, the present invention can be applied to circuit substrates, which are not multilayered, and
5 other various electronic components.

~~THIRD EMBODIMENT~~

Fig. 4 and Fig. 5 are drawings showing ~~an~~ another example of electronic components according to ~~ana~~ a further preferred embodiment of the present invention.

10 Fig. 4 is a perspective view showing an appearance of a chip coil 31 as an example of the above-described electronic components. Fig. 5 is a perspective exploded view showing a component body 32 of the chip coil 31 shown in Fig. 4.

The chip coil 31 is provided with an insulating substrate 33,
15 and insulator films 34, 35, 36, and 37 disposed by using a photolithography photosensitive paste (insulator photosensitive paste) according to a preferred embodiment of the present invention are laminated sequentially on this insulating substrate 33. Furthermore, conductor films 38, 39, 40, and 41 disposed by
20 using a photolithography photosensitive paste (conductor photosensitive paste) according to a preferred embodiment of the present invention are located on the insulating substrate 33 and the insulator films 34, 35, and 36, respectively.

The component main body 32 ~~is composed of these~~ preferably
25 includes the insulating substrate 33, insulator films 34 to 37, and conductor films 38 to 41. External terminals 42 and 43 are

disposed on opposed two end surfaces of the component body 32.

The ~~above-described~~ conductor films 38 to 41 are connected to each other through via hole connection portions 44 to 46 ~~disposed penetrating~~arranged to penetrate the insulator films 34 to 36, respectively, so as to form a predetermined coil pattern as a whole. In Fig. 5, the location of each of the via hole connection portions 44 to 46 is simply indicated by an alternate long and short dashed lines, and individual penetration conductors constituting via hole connection portions 44 to 46 are not shown in the drawing.

In more detail, the conductor film 38 is electrically connected to the conductor film 39 through the via hole connection portion 44 disposed in the insulator film 34. Likewise, the conductor film 39 is electrically connected to the conductor film 40 through the via hole connection portion 45 disposed in the insulator film 35. The conductor film 40 is electrically connected to the conductor film 41 through the via hole connection portion 46 disposed in the insulator film 36. The two end portions of the conductor films 38 to 41 connected to each other to form the coil pattern, as described above, that is, one end portion of the conductor film 38 and one end portion of the conductor film 41, are electrically connected to the external terminals 42 and 43, respectively.

A method for manufacturing this chip coil 31 will be described below.

As shown in Fig. 5, a photolithography photosensitive paste

(conductor photosensitive paste) according to a preferred embodiment of the present invention is applied to the insulating substrate 33 formed from, for example, alumina. For the application of this photolithography photosensitive paste

5 (conductor photosensitive paste), various methods, e.g., a screen printing method, a spin coating method, and a doctor blade method, can be used.

The photosensitive paste film (conductor paste film) applied and formed as described above is dried and, thereafter, is
10 subjected to an exposure treatment through a photomask having a predetermined pattern.

A development treatment is conducted to remove unnecessary portions of the photosensitive paste film (conductor paste film). Thereafter, for example, a spiral conductor film 38 is formed by
15 conducting a firing treatment in air under a predetermined condition.

The photolithography photosensitive paste (insulator photosensitive paste) according to a preferred embodiment of the present invention is applied to the insulating substrate 33 while
20 covering the conductor film 38. A method similar to that in the above-described case of application of the conductor photosensitive paste can be used for this coating.

The photosensitive paste film (insulator paste film) formed as described above is dried. Subsequently, the resulting
25 photosensitive paste film (insulator paste film) is subjected to an exposure treatment through a photomask having a predetermined

pattern in order to form a hole having a diameter of, for example, about 50 μm (not shown in the drawing) and being used for a via hole connection portion 44.

5 A development treatment is conducted to remove unnecessary portions. Thereafter, for example, an insulator film 34 having a hole for the via hole connection portion 44 is formed by conducting a firing treatment in air under a predetermined condition.

10 A conductor paste is filled in the above-described hole for the via hole connection portion 44, and drying is conducted, so that the via hole connection portion 44 is formed in the insulator film 34.

15 A spiral conductor film 39 is formed on the insulator film 34 by a method similar to that in the above-described case of formation of the conductor film 38.

Alternatively, the hole of the via hole connection portion may be filled in with the conductor paste and the photosensitive paste film (conductor paste film) may be formed by applying the conductor paste once, followed by exposure and development.
20 Thereafter, the via hole conductor and the conductor film may be fired simultaneously.

Subsequently, the insulator film 35, the conductor film 40, the insulator film 36, and the conductor film 41 are formed sequentially by a method similar to that described above. After
25 the insulator film 37 used for protection is formed, the external terminals 42 and 43 are formed, so that the chip coil 31

exhibiting an appearance as shown in Fig. 4 is completed.

According to the above-described manufacturing method, the photolithography photosensitive paste (insulator photosensitive paste) of a preferred embodiment of the present invention is used
5 for forming the insulator films 34 to 37. Therefore, in particular, fine holes for the via hole connection portions 44 to 46 to be disposed in the insulator films 34 to 36 can simply and easily be formed with excellent precision with respect to the shape and the location.

10 Likewise, since the conductor films 38 to 41 are formed by using the photosensitive paste (conductor photosensitive paste) of a preferred embodiment of the present invention, fine and high-density patterns can simply and easily be provided to these conductor films 38 to 41 with high precision. In particular,
15 thick conductor films 38 to 41 can easily be formed as compared with those in the case where a usual screen printing method or the like is applied. Consequently, the chip coil 31 is allowed to have excellent high-frequency properties.

It is also possible to use the photosensitive paste
20 according to various preferred embodiments of the present invention for only one of the conductor photosensitive paste and the insulator photosensitive paste.

The present invention is not limited to the above-described embodiments, and various applications and modifications can be
25 made within the scope of the invention.

~~Industrial Applicability~~

According to various preferred embodiments of the present invention, it ~~becomes~~is possible to ~~form~~ efficiently form via photolithography a thick film pattern having a large thickness and exhibiting high dimension precision and high shape precision ~~by photolithography~~ and, by extension, it becomes possible to produce high-performance, highly reliable ceramic multilayer substrates, chip coil components, and the like, efficiently.

Therefore, the present invention can be widely applied to various electronic components and methods for manufacturing them.